





IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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Wenhui Mei 10/064 156 Docket No.: 22397.324

Serial No.: 10/064,156

Examiner: Zoila E. Cabrera

Filed:

June 14, 2002

Art Unit: 2125

For:

Modified Photolithography §
Movement System §

Conf. No.: 5103

REQUEST FOR PERMISSION TO WITHDRAW AS ATTORNEY OF RECORD

Commissioner for Patents PO Box 1450 Alexandria, VA 22313-1450

Dear Sir:

I, the attorney signing below, respectfully request permission to withdraw from all further responsibility in this case in accordance with 37 CFR § 10.40(c)(5). I am signing below on behalf of all the other attorneys of record listed in the declaration and power of attorney filed in this case.

I respectfully request that the attorneys of record be granted permission to withdraw from all further responsibility in this case in accordance with 37 CFR § 1.36.

The basis for the request for withdrawal is 37 CFR § 10.40(c)(5), namely, my Client knowingly and freely assents to termination of my employment.

All papers and property concerning this patent have been delivered to the following:

Mr. Hisazumi Ono Ono & Associates Nippon Shuzo Building 1-21, Nishi-Shimbashi 1-chome Minato-Ku, Tokyo 105-0003 JAPAN

Status of subject case: Pending Application

The undersigned respectfully requests approval. This form submitted in TRIPLICATE.

Respectfully submitted,

Date: 3-6-06

David M. O'Dell Reg. No. 42,044

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